

# FIB (Helios)

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The Helios NanoLab 600 has been designed for obtaining highend images during failure analysis where the majority of the sample needs cross-sectioning. In addition to its flexible sample-preparation capabilities, the Helios NanoLab 600 delivers three-dimensional imaging so that you can quickly and efficiently locate and view device features from different angles. Patented beam chemistries can also be used to highlight interface layers for imaging in the system, getting you the most accurate data.

## Model

FEI (Helios NanoLab 600)

## Specifications

- Source : Schottky FEG
- Resolution : 1.0 nm (15 kV)
- Magnification : 30 ~ 1,280,000 X
- Accelerating voltage : 1 ~ 30 kV

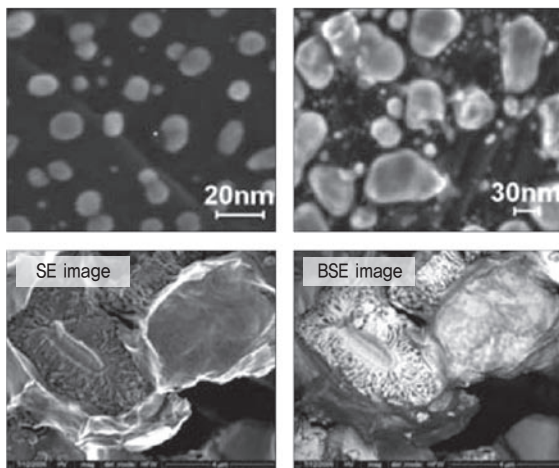
## Applications

- SE / BSE / Ion image
- STEM image
- Slice & View
- Cryo-stage
- EBSD
- EDS
- Nano patterning

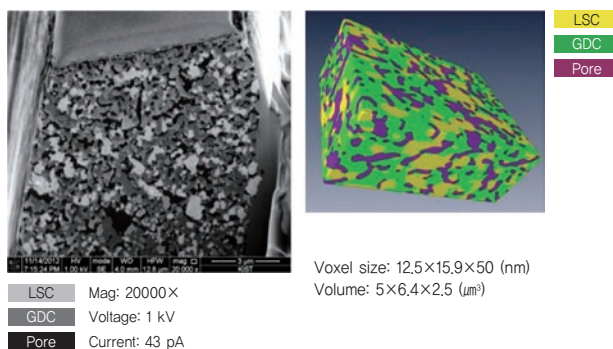


**Location** L5115F Tel.02-958-5539

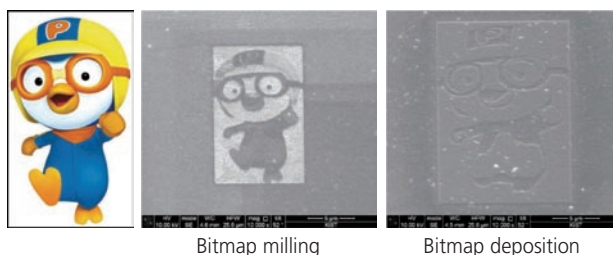
## Electron image



## 3D slice & view



## Integrated advanced nano patterning



Bitmap milling

Bitmap deposition